
Plasma and Thermal Processes for Materials Modification, Synthesis, and Processing

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Table of Contents

<i>Preface</i>	<i>iii</i>
(Invited) Nanostructures Growth by Oxidation of Metallic Alloy Thin Films with Atmospheric Pressure Remote Plasma <i>A. Imam, T. Gries, K. Hussein, M. Amati, T. Belmonte</i>	1
(Invited) Deep Silicon Etching - Increasingly Relevant >20 Years on! <i>D. Thomas, M. Muggeridge, J. Hopkins, N. Launay, H. Ashraf, T. Barrass</i>	9
Environmental-Friendly Fluorine Mixture for CVD Cleaning Processes to Replace C ₂ F ₆ , CF ₄ and NF ₃ <i>R. Wieland, M. Pittroff, J. Boudaden, S. Altmannshofer, C. Kutter</i>	23
Perfect Separation of Hybrid Orientation Structure of CeO ₂ (100) and (110) Regions Grown on Silicon on Insulator Substrates with Lithographically Formed Trenches <i>T. Inoue, S. Shida</i>	35
Author Index	47